13 JUN 2002

20020035244

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau

162162

(43) International Publication Date
28 June 2001 (28.06.2001)

PCT

(10) International Publication Number
WO 01/46998 A1

(51) International Patent Classification[7]: H01L 21/00

(21) International Application Number: PCT/US00/35066

(22) International Filing Date:
20 December 2000 (20.12.2000)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
09/470,676 23 December 1999 (23.12.1999) US

(71) Applicant *(for all designated States except US)*: **LAM RESEARCH CORPORATION** [US/US]; 4650 Cushing Parkway, Fremont, CA 94538 (US).

(72) Inventors; and

(75) Inventors/Applicants *(for US only)*: **PASCAL, Roy, Winston** [US/US]; 30770 Oxford Way, Union City, CA 94587 (US). **BLIVEN, Brian, M.** [US/US]; 416 Conestoga Way, San Jose, CA 95123 (US).

(74) Agent: MARTINE, Peter, B.; Martine, Penilla & Kim, LLP, Suite 170, 710 Lakeway Drive, Sunnyvale, CA 94085 (US).

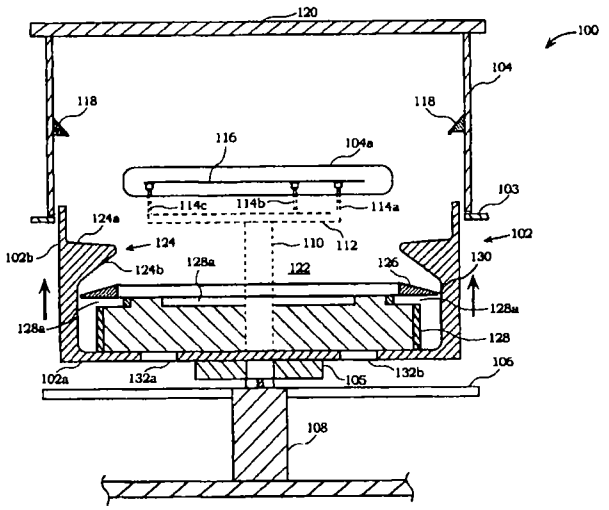
(81) Designated States *(national)*: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW.

(84) Designated States *(regional)*: ARIPO patent (GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG).

Published:
— *With international search report.*
— *Before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments.*

[Continued on next page]

(54) Title: BOWL, SPIN, RINSE, AND DRY MODULE, AND METHOD FOR LOADING A SEMICONDUCTOR WAFER INTO A SPIN, RINSE, AND DRY MODULE



(57) Abstract: A bowl (102) includes a bottom wall (102a) having a generally circular shape. A sidewall (102b) extends upwardly from the bottom wall (102a) to define a cylindrical chamber (122). The sidewall (102b) has a projection (124) that extends into the cylindrical chamber (122). The projection (124) has a top surface (124a) that defines a step in the cylindrical chamber (122) and a sloped surface (124b) that extends between the top surface and an inner surface of the sidewall (102b). The top surface (124a) of the projection (124) is sloped slightly downwardly. The sloped surface (124b) of the projection (124) is oriented relative to the top surface (124a) such that extensions of the top surface and the sloped surface define an angle in a range from about 30 degrees to about 45 degrees. A spin, rinse, and dry module (100) including the bowl (102) and a method for loading a semiconductor wafer into a spin, rinse, and dry module also are described.

WO 01/46998 A1

ACTION

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.